



Angle-resolved photoemission study of the antimony:allium arsenide interface using synchrotron radiation

by James Russell Myron

A thesis submitted in partial fulfillment of the requirements for the degree of Doctor of Philosophy in Physics

Montana State University

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Abstract:

The electronic properties of the overlayer-semiconductor interface system GaAs(110)+Sb(0),p(1x1) where  $0 = 1/2-2$  ML, are studied with synchrotron radiation-based polarization -dependent angle-resolved ultra-violet photoemission spectroscopy (PARUPS).

Two core level effects are reported, Sb-4d core binding energy shifts and the Sb-4d threshold effect. The binding energy shifts of the Sb-4d core are analyzed with curve fitting procedures and indicate the existence of two inequivalent Sb bonding sites, one on Ga and the other on As. The antimony core threshold effect is observed in angle-resolved constant final energy spectroscopy (ARCFS), photoemission yield spectroscopy, and electron energy loss spectroscopy data at energies of 32.5 and 33.75 eV. This is an Auger decay mechanism (non-excitonic) which involves the Sb-4d core and an empty Sb-derived surface state  $S7'$ . The energy of  $S7'$  is inferred to be 1.18 eV above the valence band maximum (VBM).

Valence band measurements were performed with normal emission EDC and ARCFS spectra. Transitions before and after Sb evaporation were mapped onto the theoretical energy bands. A phenomenon, the characteristic amplitude effect, is reported wherein bulk band transition amplitudes are changed by the ordered monolayer. The effect is independent of light polarization, but depends on the initial states. Evidence for non-uniform band shifting is seen in EDC spectra for  $h\nu = 60$  eV where the surface contribution to photoemission is more dominant. In the ARCFS study, a new GaAs+Sb interface state  $S4'$  3 eV below the VBM, is identified for  $A\backslash MP$  and  $A\backslash\backslash MP$ . The Sb-derived surface state  $S5$  near the VBM is observed. A GaAs surface state  $M2$ , detected at the M-point, is located 1.8 eV below the VBM. Bulk band state  $B3$  has initial state in valence band 2 and shows the same characteristic amplitude effect which was studied at normal emission.

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**A thesis submitted in partial fulfillment  
of the requirements for the degree**

**of  
Doctor of Philosophy  
in  
Physics**

**MONTANA STATE UNIVERSITY  
Bozeman, Montana**

**June 1988**

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This thesis has been read by each member of the thesis committee and has been found to be satisfactory regarding content, English usage, format, citations, bibliographic style, and consistency, and is ready for submission to the College of Graduate Studies.

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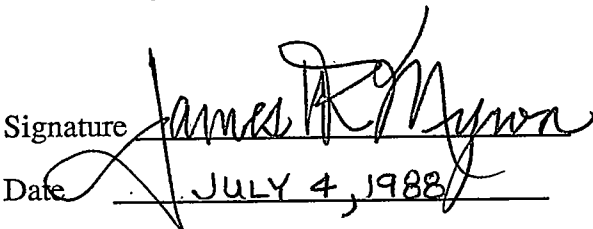
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James R. Myron  
JULY 4, 1988

This thesis is dedicated in memory of my father, Russell "Babe" Gordon Myron. His encouragement and interest in my education was a positive force from grade school through graduate school. While I was growing up, Babe would often take on all the farm chores, in order to permit me to work on my lessons. As a successful Montana farmer, his perseverance and aspiration to excellence in his endeavors were a trademark. I strived for these ideals throughout the long process of measurement, analysis, and study. My only regret is that he is not here for the thesis completion. But somehow, I feel, he knows its done.

## VITA

James Russell Myron was born in Sidney, Montana on November 21, 1952, the son of Russell Gordon and Doris Bodil Myron. He has an older brother, Gordon, and two sisters, Patricia and Cheryl.

Jim attended elementary school at a two-room rural school in the small farming community of Crane, Montana. Later he graduated as Valedictorian of the Class of 1971 from nearby Sidney Senior High School. Summers and weekends were spent helping on the family farm near Crane in the Lower Yellowstone Valley throughout high school and undergraduate school years. He started college at Montana State University in September 1971. A Bachelor of Science degree in physics was obtained in June of 1976 and a B.S. degree in mathematics was received the following year. 1975 was spent touring Europe. After starting graduate school at M.S.U. in January, 1978, he joined Dr. G.J. Lapeyre's photoemission research group. A Master of Science degree was obtained in physics in June of 1980.

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## ABSTRACT

The electronic properties of the overlayer-semiconductor interface system GaAs(110)+Sb( $\theta$ ),p(1x1) where  $\theta = 1/2$ -2 ML, are studied with synchrotron radiation-based polarization -dependent angle-resolved ultra-violet photoemission spectroscopy (PARUPS).

Two core level effects are reported, Sb-4d core binding energy shifts and the Sb-4d threshold effect. The binding energy shifts of the Sb-4d core are analyzed with curve fitting procedures and indicate the existence of two inequivalent Sb bonding sites, one on Ga and the other on As. The antimony core threshold effect is observed in angle-resolved constant final energy spectroscopy (ARCFS), photoemission yield spectroscopy, and electron energy loss spectroscopy data at energies of 32.5 and 33.75 eV. This is an Auger decay mechanism (non-excitonic) which involves the Sb-4d core and an empty Sb-derived surface state  $S'_1$ . The energy of  $S'_1$  is inferred to be 1.18 eV above the valence band maximum (VBM).

Valence band measurements were performed with normal emission EDC and ARCFS spectra. Transitions before and after Sb evaporation were mapped onto the theoretical energy bands. A phenomenon, the characteristic amplitude effect, is reported wherein bulk band transition amplitudes are changed by the ordered monolayer. The effect is independent of light polarization, but depends on the initial states. Evidence for non-uniform band shifting is seen in EDC spectra for  $h\nu = 60$  eV where the surface contribution to photoemission is more dominant. In the ARCFS study, a new GaAs+Sb interface state  $S_4$ , 3 eV below the VBM, is identified for  $A_{\perp}MP$  and  $A_{\parallel}MP$ . The Sb-derived surface state  $S_5$  near the VBM is observed. A GaAs surface state  $M_2$ , detected at the  $\bar{M}$ -point, is located 1.8 eV below the VBM. Bulk band state  $B_3$  has initial state in valence band 2 and shows the same characteristic amplitude effect which was studied at normal emission.

## CHAPTER 1

## STATEMENT OF THE PROBLEM

In its most general form, the thesis problem was to understand better the properties of ordered overlayer-semiconductor interfaces by investigation of a specific model system. This model system should possess the ideal interface properties of junction abruptness, chemical stability, and structural order.

It would be necessary to prepare this interface reliably and measure its electronic properties *in situ*, with polarization-dependent angle-resolved ultra-violet photoemission spectroscopy (PARUPS) using synchrotron radiation. Of principal importance would be identification of overlayer-induced interface states. Characterization of these states would allow an experimental check on existing theoretical calculations. However, general exploration of any interface associated phenomena would be valuable in furthering our understanding of these interfaces, including core electron and bulk electron behavior.

In order to study the model interface system adequately, completion of the design and construction of a new photoemission experimental system with advanced PARUPS capabilities would be necessary.



## CHAPTER 2

## INTRODUCTION

"During the last thirty-five years much experimental evidence has been brought to bear upon the phenomenon that a large current will pass in one direction and small current, if any at all, in the opposite direction, through contacts of certain dissimilar solids." (Hartsough 1914).

This quotation refers to the rectification effect, which lay at the heart of the theory of metal-semiconductor (MS) interfaces. The MS interface was the principal focus of this thesis. Several MS theories have been proposed over the years (Schottky 1939, Bardeen 1947, and Brillson 1982), however today no single theory correctly predicts the complete behavior of even simple interfaces.

Even though interface related work has been done for over one hundred years, the study and characterization of solid state interface systems is currently a rapidly growing field of surface science. The basic research community has investigated the surface and bulk properties of clean crystalline materials for the last several years and they are generally regarded as understood (Weaver 1986). We are now in a good position to take the next logical step; examination of the bonding region between dissimilar materials - the interface. For basic science, it affords the opportunity to extend many ideas, including chemisorption on semiconductors, semi-classical junction models, and band bending theories (Dalven 1980). For applied science and microelectronics, the importance cannot be overstated. Within this decade, the characteristic gate size of electronic

integrated circuits will move into the submicron regime and as the surface to volume ratio of gates becomes larger, interface effects will play a significant role in device performance (Harris 1984).

For compound semiconductors, the chemical and electrical behavior at MS interfaces is very complex (Brillson, 1982) and often occurs over large microscopic distances (tens of angstroms) as opposed to an abrupt interface. The metal atoms can interact strongly with the clean semiconductor to produce two chemically distinct regions with varying properties. First, the reaction region is where new metal-cation or metal-anion bonds are formed. And second, the interdiffusion region is caused by either an outdiffusion of semiconductor atoms through the metal (*e.g.*, InAs(110)+Au) or metallic indiffusion (*e.g.*, GaAs(110)+Au) towards the semiconductor.

According to Brillson, it is the chemical reactivity of the metal with the semiconductor which governs, through interdiffusion, the interface thickness. Empirically, the stronger the metal-anion bonding, the more abrupt will be the interface.

Finding a good model system without the complications noted above was desirable in order to study the fundamental interactions occurring at the interface. The interface system chosen was the cleaved (110)-face of gallium arsenide GaAs, with overlayers (1/2-2 ML) of antimony Sb, deposited at room temperature. This system, GaAs(110)+Sb,p(1x1), was a good model system for the following reasons:

- (1) GaAs(110) is a well understood and technologically important material. (Blakemore 1987, Ferry 1985).
- (2) Sb grows as an ordered, epitaxial overlayer at room temperature on cleaved GaAs(110) (Skeath 1982 p.13).

- (3) GaAs(110)+Sb forms an abrupt interface with little diffusion of Sb into the bulk or Ga/As out to the surface region, which is not the case for many other metal-GaAs systems (Lin *et al.* 1987)
- (4) The surface unit net is preserved in size and mirror symmetry when going from GaAs, *as-cleaved* to the overlayer system.
- (5) The antimony on the surface is in a single crystal phase and resists oxidation compared to GaAs, *as-cleaved*, since the new surface has no unsatisfied bonds.
- (6) Multiple layers of antimony will thermally desorb for temperatures between 250° C and 350° C (Carelli and Kahn 1982).
- (8) Important theoretical calculations of the electronic structure have been performed by Bertoni *et al.* (1983) and Mailhoit *et al.* (1985).

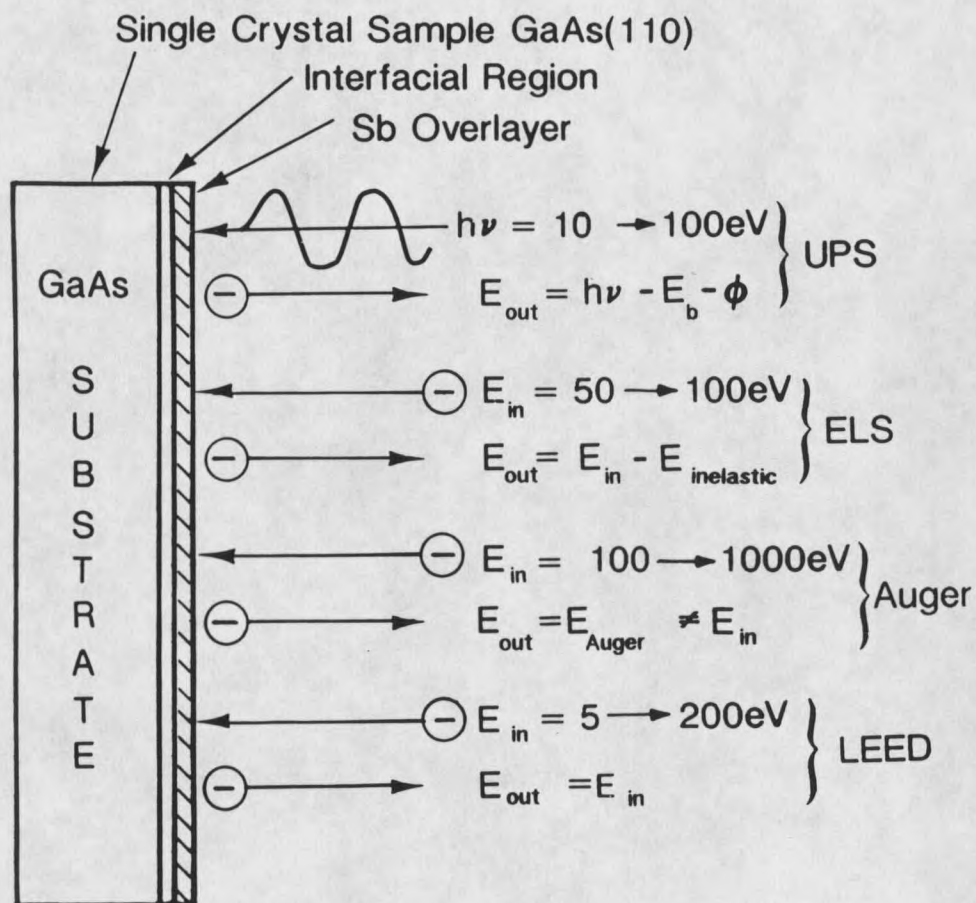
## CHAPTER 3

## THEORY OF PHOTOEMISSION

Several surface analytical measurement techniques were used in the course of investigations of GaAs(110)+Sb. Figure 1 schematically defines these various techniques and indicates the general characteristics of each.

At the top is Ultra-violet Photoemission Spectroscopy (UPS), which is a subclass of Photoemission Spectroscopy (PES) where the incident particle is a photon ( $h\nu = 10$  to  $100$  eV). It is a highly surface sensitive method with an investigation depth of  $5$  to  $18$  Å (1-3 ML). By conservation of energy, the photoelectron ejected from the sample has a energy equal to the photon energy reduced by the binding energy  $E_b$  of the electron when it was in a bound state and by the work function  $\phi$  of the sample.

The second technique in Figure 1 is Electron Loss Spectroscopy (ELS) which uses a low kinetic energy incident electron (50-100 eV) as the incident particle and measures the energy of the emitted electrons. These spectra have an elastic peak, composed of the electrons which undergo elastic Coulomb scattering, and a wide variety of energy loss features due to plasmons (collective charge excitations), Auger transitions, and other inelastic processes. We employed ELS first as a nondestructive technique to quantify the thickness of the antimony overlayers which were evaporated onto the GaAs crystal. Latter, ELS was found to reveal new effects which could be related to the formation of the overlayer. These new effects which were revealed in the ELS data will be discussed in the section on the antimony core threshold studies (Chapter 6).



**Figure 1. Surface analytical spectroscopies used in this work.** The output particle of each technique is an electron of kinetic energy  $E_{\text{out}}$ . The input "probe" particle is either a photon of energy  $h\nu$  (UPS) or an electron of energy  $E_{\text{in}}$ .

Auger Electron Spectroscopy (AES) was the third technique used. The basis for AES is a nonradiative transition where a vacancy (caused by ionization by an incident particle) in an inner shell of an atom is filled via the two-electron Auger process. Here an electron fills the vacancy and releases a characteristic amount of energy to a correlated electron (the Auger electron). Subsequently, this Auger electron is ejected from the sample with a unique energy  $E_{Auger}$  related to the binding energies of the atomic orbitals involved in the process. The Auger transition energy is rather like a unique chemical "fingerprint". At low kinetic energies (100 eV) the technique is very surface sensitive, since a low-energy Auger electron can escape only from the first few sample layers. Although AES has quantitative capabilities (Carlson 1975, Feldman and Mayer 1986), it was only used in this work when the overlayer sample could be sacrificed, since Zurcher (1982) had reported electron beam damage in GaAs(110)+Ge samples.

The last technique, Low Energy Electron Diffraction (LEED), was used routinely to characterize the sample surface before and after overlayer growth and to orient the symmetry axis of the crystal. LEED relies on elastic scattering and diffraction of slow electrons (50-200 eV) to determine the surface net and therefore the surface order. Of all these techniques, UPS was the principal method employed in this research work and will be the subject of the remainder of this chapter.

### The Photoemission Process

Photoemission has a rich heritage in the physics community. The photoelectric effect was discovered by Hertz in 1887 (Weidner *et al.* 1968). An explanation of the effect, which postulated the quantization of light, was proposed by Einstein in 1905. Later, Millikan, through careful experimentation, verified Einstein's theory of the

photon, and constructed one of the first photoemission systems (Trigg 1975). Today the effect is exploited as a powerful spectroscopic technique for studying the quantum properties of solids. Spicer (1982) gives an interesting account of the role photoemission has played in the development of surface science.

A closely related research field to PES is the optical properties of solids (Wooten 1972) where the optical reflectance of a sample is measured as a function of the photon energy  $h\nu$  of the incident light. The optical spectra manifest excitation processes within the material, but photoemission is more specific since it examines the electrons which have escaped from the sample as a result of irradiation by monochromatic light. Therefore PES, unlike optical reflectivity, gives the final state energy of the excitation as well as the excitation energy, which is of importance in understanding the electronic and optical properties of solid materials.

### Experimental Aspects

Consider an arrangement as shown in Figure 2. Light (photons) impinges on the surface in a direction  $(\theta_i, \phi_i)$ , with energy  $h\nu$  and polarization given by the vector potential  $\vec{A}$ . The photoelectron ejected into the vacuum travels in a direction  $(\theta_p, \phi_p)$  with a kinetic energy  $E_k$  and momentum  $\vec{p}$  towards the detector.

The detector acts as a directional kinetic energy bandpass filter. The energy passband is termed the detector's energy window. By scanning the energy window and keeping a fixed direction, a histogram of the number of photoelectrons at each kinetic energy value, called an Angle-Resolved Energy Distribution Curve (AREDC) results. A hypothetical EDC is shown in Figure 2, and is composed of several parts:

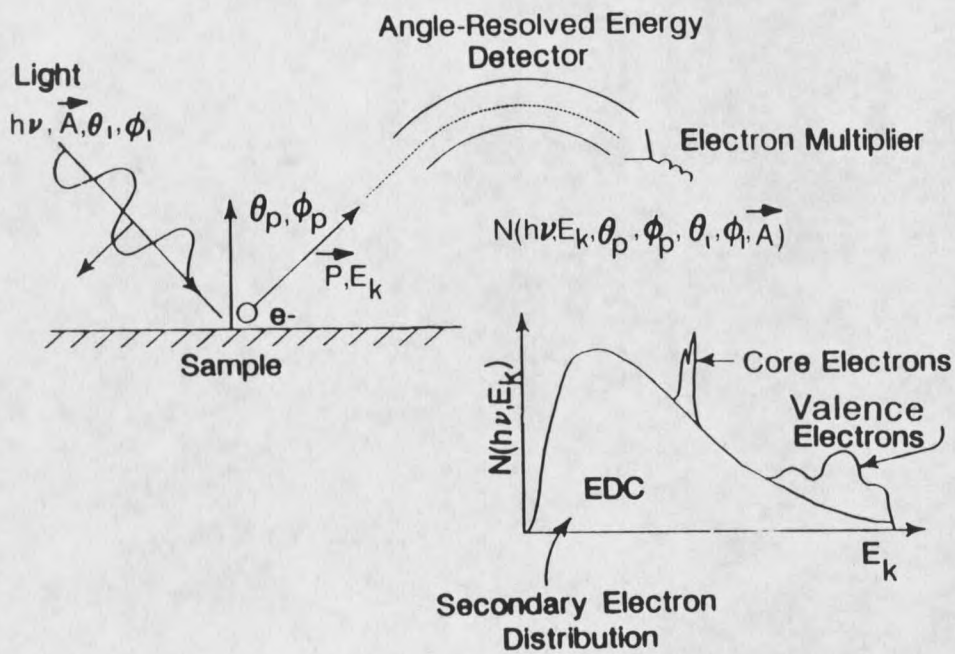


Figure 2. Generalized concept of photoelectron spectroscopy. Shining light onto the sample produces photoemitted electrons which are energy analyzed by the angle-resolving detector, resulting in an EDC.



- (1) The secondary electron distribution (SED) is a broad background curve with a long decaying tail resulting from inelastic scattering of the photoelectrons within the sample (Caroli 1973). Generally, this background is subtracted from the EDC in preliminary processing. These electrons are amongst the slowest-velocity electrons in the EDC and, because of their rather featureless nature, they are not of interest to us here.
- (2) The core electron peaks are rather sharp features which result from electrons excited from deep core states. These core states are the tightly bound inner electronic shells of the atom. The studies presented in Chapter 6 pertain to interface related effects manifested in the core states.
- (3) The valence electron features manifest the electronic bonding or band structure of the material and directly reveal the behavior of the solid; in this case, the interface system. These states are very sensitive to the many acquisition parameters of the experiment. When the detector is moved to a new analysis angle, the valence features will generally change and in the case of GaAs, the changes will often be dramatic, since the band structure is complex. Chapter 7 will cover several experiments which were designed to study these features.

Photoemission spectroscopy is inherently very rich in information. The purpose of much of the effort in a photoemission experiment is to define and measure the many parameters. The photocurrent  $J$  is a function of at least ten parameters, most of them related to the source and detector configuration:

$$J = J(h\nu, \theta_A, \phi_A, \theta_I, \phi_I; E_k, \theta_P, \phi_P, S; X) \quad (1)$$

where

the source parameters are:

photon energy:  $h\nu$ .

polar angle of the light's vector potential,  $\vec{A} : \theta_A$ .

azimuthal angle of the light's vector potential,  $\vec{A} : \phi_A$ .

polar angle of the light's propagation direction:  $\theta_l$ .

azimuthal angle of the light's propagation direction:  $\phi_l$ .

the detector parameters are:

kinetic energy of the photoelectrons:  $E_k$ .

polar angle of the photoelectron's momentum vector,  $\vec{p} : \theta_p$ .

azimuthal angle of the photoelectron's momentum vector,  $\vec{p} : \phi_p$ .

Lastly, the sample parameters are:

The photoelectron's spin polarization  $s$ , which we will ignore, and a manifold of sample characteristics which complicate the method. They have been lumped under the  $X$  factor. These include the type of material, crystal face, sample preparation, and surface cleanliness. Careful experimental technique is of paramount importance here in order to characterize the system.

Experimentally, we fix all the acquisition parameters (source and detector), usually adjusting only the photon energy  $h\nu$  and scanning the kinetic energy  $E_k$ . This is the angle-resolved energy distribution curve (AREDC) mode of photoemission, resulting in a curve like shown in Figure 2. With this AREDC data (angle-resolved and energy-analyzed photocurrent), we try to determine the properties of the material. Using theoretical

models of photoemission as a basis (*e.g.* the three-step model) coupled possibly with theoretical calculations of the electronic structure of the system, we relate the data back to properties and excitation mechanisms of the material. In particular, our goal is to understand better the nature of the Ga-Sb and As-Sb bonding and how it relates to properties of the GaAs+Sb interfacial region.

Up to now we have only talked about the empirical aspects of photoemission, namely, measuring the kinetic energy and momentum of photoemitted electron after light has irradiated a material. A conceptual and theoretical understanding of the physical processes occurring within the sample, which result in our observations, is important in order to infer the properties of the material from the rather complex photoemission data. Two of the most popular models proposed for describing these processes are the microscopic one-step model (Feibelman and Eastman 1974) and the semiphenomenological three-step model (Spicer 1958). The one-step model is an elegant quantum mechanical approach, insofar as it treats photoemission as single wave function phenomena. The semi-classical three-step model works well for low excitation energies and is quite intuitive. The simpler three-step model has several shortcomings (*e.g.* surface effects) which the one-step model does not have. However, both models have importance in understanding the current research and will be used.

### Three-step Model of Photoemission

The independent steps in the three-step model are (1) photoabsorption by a bound electron, (2) transport of that electron to the surface, and (3) its escape into the vacuum. Consequently, the photocurrent in Equation 1 factors into three parts:

$$J(E_f, h\nu) = P(E_f, h\nu)T(E_f, h\nu)D(E_f, h\nu) \quad (2)$$

where P, T, and D are the photoabsorption, transport, and escape factors, respectively. The final energy of the photoelectron is  $E_f$ .

Figure 3 puts the three-step model in context with the notions of the solid/vacuum interface, the VB and CB density-of-states, and the three acquisition modes of photoemission. It shows a hypothetical semiconductor, analogous to GaAs, with a shallow valence band density-of-states B (*e.g.*, VBs 2,3,4 in GaAs), a deeper VB feature called C (*e.g.*, VB 1 in GaAs), and a sharp core state called D (Ga-3d). The conduction band has a abrupt edge at the conduction band minimum and various conduction band structures. Of these, feature A will be of interest here. We have taken the Fermi level to be at mid-gap as it would be for an intrinsic semiconductor. The vertical direction represents energy, whereas the horizontal takes on many connotations depending on the curve in question. To the left of the solid/vacuum interface are the processes which occur inside the solid. Those to the right, like the measurement processes, happen in the vacuum.

The photoabsorption process (step 1 in Figure 3) can occur inside the semiconductor anywhere from 60 to 300 Å below the surface (Pankove 1971), because of the relatively long photon attenuation length in the solid. An electron in an initial valence band state of energy  $E_i$  absorbs a photon of energy  $h\nu$  and jumps into a final conduction band state of energy  $E_f$ . Applying this reasoning to all electrons in the B structure, produces a distribution of excited conduction band electrons called B which is identical to the valence band structure B, provided the conduction band density-of-states are not changing. The same argument applies to features C and D, however these features are not drawn in Figure 3 for clarity of presentation.

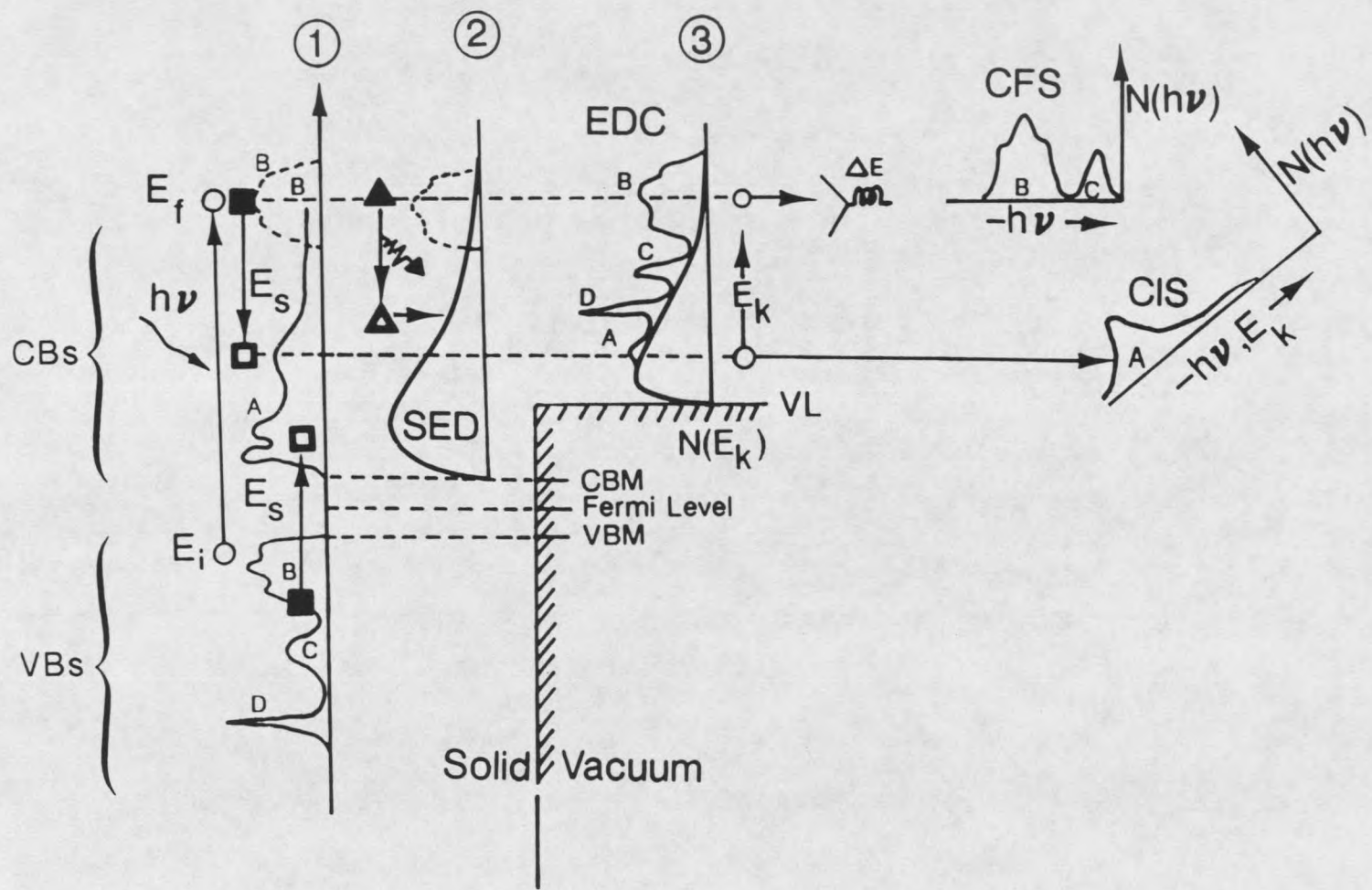


Figure 3. The three-step model of photoemission. Also shown is the relationship between the three-step model and the EDC, CFS, and CIS modes of measurement.

In a more theoretical manner, the photoabsorption factor  $P$  is derived from time-dependent perturbation theory. The effect of the photon field is represented by a time-dependent Hamiltonian  $H'(t)$ , which is weak compared to system's time-independent Hamiltonian  $H_0$ . Therefore, the total Hamiltonian is the summation of two:

$$H = H_0 + H'(t) \quad (3)$$

We are looking for approximate solutions to the time dependent Schrödinger equation.

$$H\Psi(\vec{r},t) = (i\hbar/2\pi) \frac{\partial\Psi(\vec{r},t)}{\partial t} \quad (4)$$

We can write the wave function of  $H$  as a superposition of eigenfunctions  $\psi_n(\vec{r})$  which are stationary states of  $H_0$  with eigenvalues  $E_n$  (see Equation 6).

$$\Psi(\vec{r},t) = \sum c_n(t)\psi_n(\vec{r}) \exp(-i2\pi E_n t/\hbar) \quad (5)$$

$$H_0\psi_n(\vec{r}) = E_n\psi_n(\vec{r}) \quad (6)$$

Here the expansion coefficients  $c_n$  are functions of time. By substituting Equation 5 into 4 and simplifying (Saxon 1968 p.209), we obtain the time evolution of the system through the  $c_n$ 's. The rate of change of these coefficients is proportional to  $\langle \psi_f | H' | \psi_i \rangle$ , the matrix element coupling the initial state  $\psi_i(\vec{r})$  to the final state  $\psi_f(\vec{r})$ . The transition probability that the system will go from the unperturbed initial state  $\psi_i$  to the unperturbed final state  $\psi_f$  after the interaction is  $|c_n(t)|^2$ .

Now let's consider the effect of an oscillating electromagnetic field in the form of a periodic perturbation (Wooten 1972, p. 109),

$$H' = \frac{V(\vec{r})}{2} \{e^{i\omega t} + e^{-i\omega t}\} \quad (7)$$





















































































































































































































































































































































































































































































































